

FORM PTO-1449 (Modified)		US DEPARTMENT OF COMMERCE		Docket No. 050623.134	Application No. 09/997,449		
INFORMATION DISCLOSURE CITATION in an Application (Use several sheets if necessary)				Applicant Shamim Malik et al.			
				Filing Date November 30, 2001		Group Art Unit 3773	

U.S. PATENT DOCUMENTS							
Examiner Initial	Ref. No.	Document Number	Date of Patent	Name	Class	Subclass	Filing Date if Appropriate
/MT/	A1	5,040,548	8/20/91	Yock			
	A2	5,047,050	9/10/91	Arpesani			
	A3	5,049,132	9/17/91	Shaffer et al.			
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	A14	7,056,523	6/6/06	Michal et al.			
	A15	7,077,860	7/18/06	Yan et al.			
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U.S. PATENT APPLICATION DOCUMENTS							
Examiner Initial	Ref. No.	Document Number	Filing Date	Name	Class	Subclass	Publication Date if Appropriate
	A20	09/997,449	11/30/01	Malik et al.			

U.S. PATENT APPLICATION PUBLICATION DOCUMENTS							
Examiner Initial	Ref. No.	Document Number	Date of Publication	Name	Class	Subclass	Filing Date if Appropriate
	A21	20060178738	8/10/06	Yan et al.			
	A22	20070036905	2/15/07	Kramer			
	A23	20070166496	7/19/07	Kramer			

	A24	20070184228	8/9/07	Kramer			
FOREIGN PATENT DOCUMENTS							
Examiner	Ref. No.	Document	Date of	Country	Class	Subclass	Translation Abstract
Initial		Number	Publication				Yes No
/MT/	B1	DE 19855786	6/8/00	Germany			X
	B2						
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)							
	C1	Malik et al., <i>Development of an Energetic Ion Assisted Mixing and Deposition Process for TIN_x and Diamondlike Carbon Films, Using a Co-axial Geometry in Plasma Source Ion Implantation</i> , J. Vac. Sci. Technol. A, Vol. 15, No. 6, pp. 2875-2879 (Nov./Dec. 1997).					
	C2	Malik et al., <i>Overview of plasma source ion implantation research at University of Wisconsin-Madison</i> , J. Vac. Sci. Technol. B, No. 12, Vol. 2, pp. 843-849 (Mar./Apr. 1994).					
	C3	Malik et al., <i>Sheath dynamics and dose analysis for planar targets in plasma source ion implantation</i> , Plasma Sources Sci. Technol. Vol. 2, pp. 81-85 (1993).					
	C4	Scheuer et al., <i>Model of plasma source ion implantation in planar, cylindrical, and spherical geometries</i> , J. Appl. Phys., Vol. 67, No. 3, pp. 1241-1245 (Feb. 1990).					
	C5	Shamim et al., <i>Measurement of electron emission due to energetic ion bombardment in plasma source ion implantation</i> , J. Appl. Phys., Vol. 70, No. 9, pp. 4756-4759 (Nov. 1991).					
	C6	Shamim et al., <i>Measurements of Spatial and Temporal Sheath Evolution for Spherical and Cylindrical Geometries in Plasma Source Ion Implantation</i> , J. Appl. Phys., Vol. 69, No. 5, pp. 2904-2908 (March 1991).					
EXAMINER				DATE CONSIDERED			
/Melanie Tyson/				06/18/2009			
EXAMINER: Initial if references considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							